

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Wu et al.

Serial No.: 10/672,778

Filed: September 26, 2003

For: Atomic Layer Deposition (ALD) Method with  
Enhanced Deposition Rate

Group Art Unit: 2891

Examiner: Smith, Bradley

Confirmation No.: 9717

TKHR Docket: 252016-3000


Top-Team: 0503-8501DUS

## CERTIFICATE OF FACSIMILE TRANSMISSION UNDER 37 CFR §1.8

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being transmitted on the date indicated below via facsimile to the United States Patent and Trademark Office, Technology Group 2100, facsimile number (571) 273-8300. Total number of pages in this transmission: 1

October 18, 2005

Date

  
Hui Chin BarnhillRESPONSE TO RESTRICTION/ELECTION REQUIREMENTS

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

The Office Action mailed September 22, 2005 has been carefully considered. In further response thereto, please enter the following amendments and consider the following remarks.

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